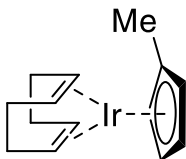


Catalog # 77-5000 (Methylcyclopentadienyl)(1,5-cyclooctadiene)iridium(I), 99% (99.9%-Ir)



Thermal Behavior:

- Melting point 38-40°C [1, 5]
- Sublimation at 95-100°C/0.05mm [1]; 30°C/0.01 Torr [2]; 50°C/0.01 Torr [5]
- TGA diagrams and data are available in [3, 5]
- Vapor pressure: 0.08 Torr/80°C; 0.28 Torr/120°C [4]; vapor pressure diagram is available in [5]

Technical Notes:

1. ALD/CVD precursor for Iridium thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Ir IrO <sub>2</sub>	CVD	100°C	0.001-0.1 Torr 0.05-0.1 Torr	H <sub>2</sub> O <sub>2</sub>	300-400°C 300-350°C	6
IrO <sub>2</sub>	CVD CVD	RT, Toluene 90-110°C	1-30 Torr 20-50 Torr	O <sub>2</sub>	250-500°C 350°C	7 8-10

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